



Lab Manual



Chapter 4.1

Summary of Standard Photoresists Available

	Standardized Photoresists at the Marvell Nanofabrication Laboratory						
	UV210-0.6	UV210-0.3	UV26-3.0	OiR-906-12	SPR-220-7.0	S1818	OCG 825 35CS
Producer	Dow Chemical	Dow Chemical	Dow Chemical	FujiFilm	Dow Chemical	Dow Chemical	FujiFilm
Wavelength	DUV	DUV	DUV	i-line **	i-line **	g-line *	g-line *
Dispense Location	(svgcoat6)	(svgcoat6)	(svgcoat6)	(svgcoat 1 & 2)	(svgcoat 1 & 2)	(headway 1 & 2)	(svgcoat 1 & 2)
Viscosity	14 cst	8 cst	112 cst	14 - 20 cst	390 cst	39 cst	34 - 37 cst
Type	Positive	Positive	Positive	Positive	Positive	Positive	Positive
Standard Thicknesses	0.42, 0.90 μm	0.38 μm	3.3, 4.7 μm	1.2, 1.7, 2.1, 2.8 μm	10.0 μm	1.65 μm	1.3, 2.3 μm
Developer	MF-26A	MF-26A	MF-26A	OPD-4262	MF-26A	Microposit MF-319	OCG 934 3:2
Stripper	PRS-3000	PRS-3000	PRS-3000	PRS-3000	PRS-3000	PRS-3000	PRS-3000

* May also be used with i-line

** May also be used with g-line